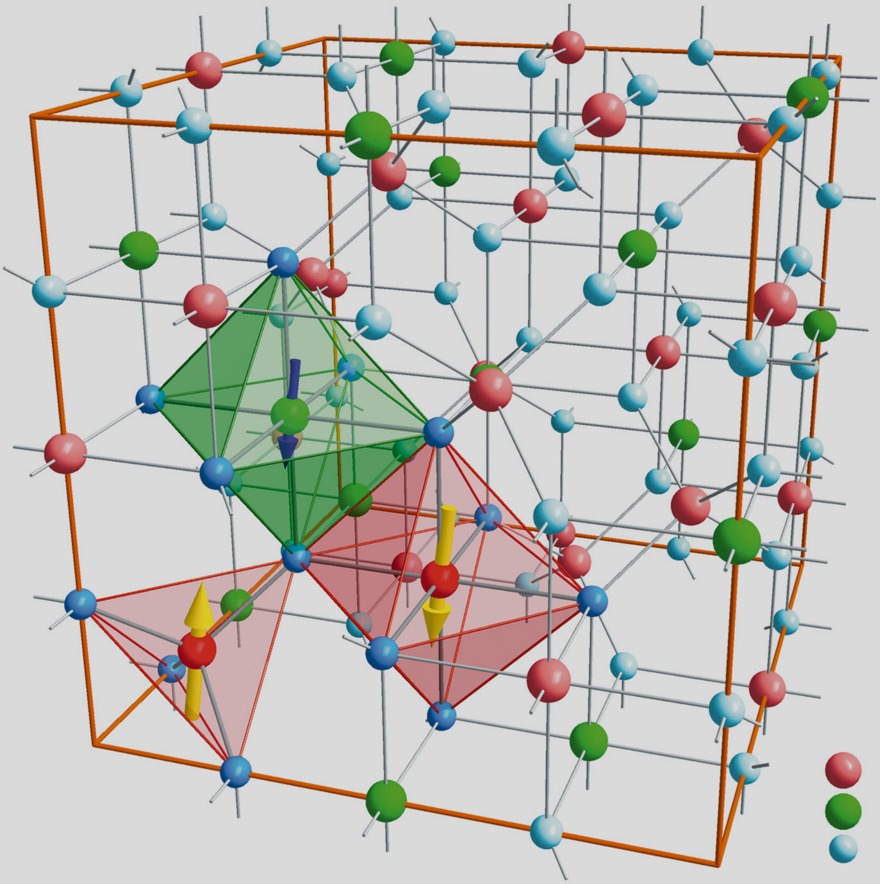
Magnetic, structural, and electronic properties of $NiFe_2O_4$ ultrathin films

Michael Hoppe



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